Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
LI	7	(Bernard in: or Dijon in: or Rafin, in:) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:51
L3	2	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 12:44
L4	2	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO, sub.2") same (vacuum or evaporat\$6 or (electron adj (beam or gun))))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 12:45
L5	13	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same (vacuum or evaporat\$6 or (electron adj (beam or gun))))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:46
L6	10	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same (cold or (room adj temperature) or cool\$4))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:55
L7	0	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same (cold or (room adj temperature) or cool\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 12:47
L8		(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same ("without" near3 (energy or ion or plasma or heat\$4)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 12:59
L9	1	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same ("without" near3 (energy or ion or plasma or heat\$4)))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:48

L10	179	(Bernard.in. or Dijon.in. or Rafin. in.) and (hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2")	US-PGPUB; USPAT	OR	ON	2006/03/14 12:48
L11	7	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium ad) \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:48
L12	2	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 12:48
L13	13	(Bernard in: or Dijon in. or Rafin in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (vacuum or evaporat\$6 or (electron adj (beam or gun))))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:48
L14	10	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2") same (cold or (room adj temperature) or cool\$4))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:48
L15	1	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO, sub.2") same ("without" near3 (energy or ion or plasma or heat\$4)))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:48
L16	155	L10 not (L11 or L12 or L13 or L14 or L15)	US-PGPUB; USPAT	OR	ON	2006/03/14 12:49
L17	34	(Bernard.in. or Dijon.in. or Rafin. in.) and (hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO, sub.2")	USOCR	OR	ON	2006/03/14 12:49
L18	4	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or ((Hf or hafnium) adj \$30xide) or HfO2 or HfO or "HfO.sub.2") same (reactive near2 evaporat\$5))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:50

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L20	7	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or ((Hf or hafnium) adj \$30xide) or HfO2 or HfO or "HfO.sub.2") same ((ambient or ambiant or room) near2 temperature))	US-PGPUB; USPAT	OR	ON	2006/03/14 12:51
L21	0	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or ((Hf or hafnium) adj \$30xide) or HfO2 or HfO or."HfO.sub.2") same ((ambient or ambiant or room) near2 temperature))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 12:51
L22	1	(Bernard.in. or Dijon.in. or Rafin. in.) and ((hafnia or ((Hf or hafnium) adj \$3oxide) or HfO2 or HfO or "HfO.sub.2") same (reactive near2 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:01
L23	367	((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO.sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density or porosity)).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 12:53
L24	217	((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO.sub.2") with (amorphous or density)).clm.	US-PGPUB; USPAT	OR	ON.	2006/03/14 13:20
L25	1	23 and (react\$5 near2 evaporat\$5).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 12:54
L26	42	23 and (cold or ((room or ambient or ambiant) adj temperature) or cool\$4).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 12:55
L27	4	23 and (("without" or "no" or "not" or absen\$5) near3 (energy or ion or plasma or heat\$4 or bombard\$6 or irradiat\$5)).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 13:10
L28	324	23 not (25 26 27)	US-PGPUB; USPAT	OR	ON	2006/03/14 13:01
L29	1	23 and ((evaporat\$5 or deposit\$5 or coat\$5 or process or vaporiz\$8 or \$4cvd or \$4pvd or sputter\$5) near6 (interrupt\$7 or plural\$6 or stop\$5 or multi or multiple or two or several) near6 cool\$5).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 13:18
L30	16	23 and ((evaporat\$5 or deposit\$5 or coat\$5 or process or vaporiz\$8 or \$4cvd or \$4pvd or sputter\$5) near6 (interrupt\$7 or plural\$6 or stop\$5 or multi or multiple or two or several or cool\$5)).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 13:19

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L31	7	((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO.sub.2") same (reactive near3 evaporat\$5)).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 13:36
L32	128	((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO.sub:2") same (cold or ((room or ambient or ambiant) adj temperature) or cool\$4)).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 13:26
L33	9	((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO.sub.2") same (("without" or "no" or "not" or absen\$5) near3 (energy or ion or plasma or heat\$4 or bombard\$6 or irradiat\$5))).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 13:27
L34	Ö	((hafnia or (hafnium ad) \$30xide) or HfO2 or HfO or "HfO.sub.2") same ((evaporat\$5 or deposit\$5 or coat\$5 or process or vaporiz\$8 or \$4cvd or \$4pvd or sputter\$5) near6 (interrupt\$7 or plural\$6 or stop\$5 or multi or multiple or two or several) near6 cool\$5)).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 13:28
L35	3	((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO.sub.2") and ((evaporat\$5 or deposit\$5 or coat\$5 or process or vaporiz\$8 or \$4cvd or \$4pvd or sputter\$5) near6 (interrupt\$7 or plural\$6 or stop\$5 or multi or multiple or two or several) near6 cool\$5)).clm.	US-PGPUB; USPAT	OR	ON	2006/03/14 13:29
L36	97	((hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO.sub.2") same ((evaporat\$5 or deposit\$5 or coat\$5 or process or vaporiz\$8 or \$4cvd or \$4pvd or sputter\$5) near6 (interrupt\$7 or plural\$6 or stop\$5 or multi or multiple or two or several or cool\$5))).clm.	USPAT	OR	ON	2006/03/14 13:35
L37	1	("5733042").PN.	US-PGPUB; USPAT	OR	OFF	2006/03/14 13:36
L38	501	(427/374.2,398.1).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 13:36
L39	4	38 and (hafnia or (hafnium adj \$30xide) or HfO2 or HfO or "HfO. sub.2")	US-PGPUB; USPAT	OR	ON	2006/03/14 13:38
L40	497	38 not 39	US-PGPUB; USPAT	OR	ON	2006/03/14 13:38

L41	2497	(427/162,164,166).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 13:50
L42	1415	(427/255.23,255.31,255.7).CCLS	US-PGPUB; USPAT	OR	OFF	2006/03/14 13:50
L43	1129	(427/294).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 13:50
L44	459	(427/419.3).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 13:50
L45	1644	(359/584,588,589,838).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 13:50
L46	6720	L41 L42 L43 L44 L45	US-PGPUB; USPAT	OR	ON	2006/03/14 13:50
L47	6720	L41 L42 L43 L44 L45	US-PGPUB; USPAT	OR	ON	2006/03/14 13:51
L48	10	L47 and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2") with (pore or porous or porous or porous or amorphus or noncrystal\$6 or (non adj crystal\$5)) with (deposit\$4 or coat\$4 or film or \$5layer or	US-PGPUB; USPAT	OR	ON	2006/03/14:13:52
L50	12	evaporat\$6 or stack or mirror)) L47 and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2006/03/14 13:52
L51	192	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:53
L52	8	L51 and ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:53

		LAST Seat		,		
L53	13	L51 and (cold or (room adj temperature) or cool\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:54
L54	2	L51 and ("without" near3 (energy or ion or plasma or heat\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14:13:54
L55	8	L51 and ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:54
L56	13	L51 and (cold or (room adj temperature) or cool\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:54
L57	2	L51 and ("without" near3 (energy or ion or plasma or heat\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:54
L58	171	L51 not (L55 or L56 or L57)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:54
L59	758	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2006/03/14 13:56
L60	24	L59 same ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	US-PGPUB; USPAT	OR	ON	2006/03/14 13:56
L61	24	L59 same (cold or (room adj temperature) or cool\$4)	US-PGPUB; USPAT	OR	ON	2006/03/14 13:56
L62	1	L59 same ("without" near3 (energy or ion or plasma or heat\$4))	US-PGPUB; USPAT	OR	ON	2006/03/14 13:57
L63	14	L59 and ((protect\$5 or damag\$5) with laser)	US-PGPUB; USPAT	OR	ON	2006/03/14 13:58
L64	3	((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or amorphus)) and (reactive near2 evaporat\$5) and ((room or ambient or ambiant) near2 temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:59

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L66	2	(((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or amorphus)) same (reactive near2 evaporat\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:59
L67		(((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or amorphus)) same (reactive near2 evaporat\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14:13:59
L68	36	(((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2")) same (reactive near2 evaporat\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:59
L69	34	L68 not L67	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 13:59
L70	3	((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or amorphus)) and (reactive near2 evaporat\$5) and ((room or ambient or ambiant) near2 temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:00
L71	.119	((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2")) and (reactive near2 evaporat\$5) and ((room or ambient or ambiant) near2 temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:00
L72	107	L71 not (L70 or L68)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:00
L73	360	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO, sub.2" or Hf2O3 or "Hf.sub.2O, sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (cool\$3 or cold or (room adj temperature)))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:01
L74	7	L73 and L47	US-PGPUB; USPAT	OR	ON	2006/03/14 14:01

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L75	4	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((reactive adj evaporat\$5) with (Hf or hafnium) with (O2 or oxygen or "O.sub. 2")))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:02
L76	33	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO; sub.2" or Hf2O3 or "Hf.sub.2O, sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((evaporat\$5) with (Hf. or hafnium) with (O2 or oxygen or "O.sub.2")))	US-PGPUB; USPAT	OR	ON	2006/03/14:14:03
L77	9	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((evaporat\$5) with (Hf or hafnium) with (O2 or oxygen or "O.sub.2")))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:04
1.7.8 H	98	\$3oxide) or HfO2 or HfO or "HfO, sub.2" or Hf2O3 or "Hf.sub.2O; sub.3" or "Hf.sub.2 O.sub.3") near3 (amorphous or amorphus) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:05
L79	52	L78 and (substrate with temperature)	US-PGPUB; USPAT	OR	ON	2006/03/14 14:05
L80	46	L78 not L79	US-PGPUB; USPAT	OR	ON	2006/03/14 14:06
L81	18	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") near3 (amorphous or amorphus) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:07

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L82	8	((hafnia or ((hafnium or Hf) near2 \$30xide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or amorphus)) same ((room or ambient or ambiant) near2 temperature)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:08
L83	475	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub:2" or Hf2O3 or "Hf.sub:2O. sub:3" or "Hf.sub:2 O.sub:3") with (silica or SiO2 or "SiO.sub:2" or SiO or (silicon adj \$30xide)) with (mirror or multilayer or (multi adj layer) or stack or reflect\$6 or (alternat\$6 near2 layer)))	US-PGPUB; USPAT	OR	ON	2006/03/14:14:08
L84	31	L83 and L47	US-PGPUB; USPAT	OR	ON	2006/03/14 14:09
L85	25	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2"))) and (temperature near2 room)	US-PGPUB; USPAT	OR	ÖN	2006/03/14 14:10
L86	34	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2"))) and (temperature with substrate)	US-PGPUB; USPAT	OR	ON	2006/03/14 14:10
L87	2	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2"))) and (temperature with substrate)	EPO; JPO; DERWENT; IBM_TDB	ÖR	ON.	2006/03/14 14:11

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L88	0	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2"))) and (temperature near2 room)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:11
L89	23	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO; sub:2" or Hf2O3 or "Hf.sub:2O; sub:3" or "Hf.sub:2 O.sub:3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub:2") same (temperature)))	US-PGPUB; USPAT	OR	ON	2006/03/14:14:12
L92	2171	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same temperature)	US-PGPUB; USPAT	OR	ON	2006/03/14 14:12
L93	45	L92 and L47	US-PGPUB; USPAT	OR	ON	2006/03/14 14:12
L94	2497	(427/162,164,166).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 14:13
L95	1415	(427/255:23;255.31,255.7).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 14:13
L96	1129	(427/294).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 14:13
L97	459	(427/419.3).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 14:13
L98	1644	(359/584,588,589,838).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/03/14 14:13
L99	6720	L94 L95 L96 L97 L98	US-PGPUB; USPAT	OR	ON	2006/03/14 14:13
L100	19	L99 and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf. sub.2O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror)).ti,ab.	US-PGPUB; USPAT	OR	ON	2006/03/14 14:13

L101	106	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:13
L102	618	amorphus)) ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O. sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or amorphus))	US-PGPUB; USPAT	OR	ON	2006/03/14:14:15
L103	56	L102 and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf of hafnium))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:15
L104	8	L102 and L99	US-PGPUB; USPAT	OR	ON	2006/03/14 14:16
L105	12	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or amorphus))	USOCR	OR	ON	2006/03/14 14:16
L106	83	("427"/\$).ccls. and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror)) and (((electron ad) beam) or (e ad) beam) or evaporat\$6 or vaporiz\$8) with (Hf of hafnium))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:17

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L107	29	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) and (("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy) with (substrate or base or workpiece or mirror or coat\$4))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:30
L108	.29	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) and (("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy) with (substrate or base or workpiece or mirror or coat\$4))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:19
L109		((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) and (("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy) with (substrate or base or workpiece or mirror or coat\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:22

L110	6	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and ((((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) same (temperature with (substrate or base or workpiece or mirror or coat\$4)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:22
111	1	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density with (determin\$9 or optimiz\$9 or optimal\$8 or based or depend\$7))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:23
L113	25	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density with (determin\$9 or optimiz\$9 or optimal\$8 or based or depend\$7))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:24
L114	25	((hafnia or ((hafnium or Hf) near4 \$30xide) or Hf02 or Hf0 or "Hf0. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density with (determin\$9 or optimiz\$9 or optimal\$8 or based or depend\$7))	US-PGPUB; USPAT	OR	ON	2006/03/14 14:25
L115	195	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density)	US-PGPUB; USPAT	OR	ON	2006/03/14 14:25
L116	170	L115 not L114	US-PGPUB; USPAT	OR	ON	2006/03/14 14:25

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L117	179	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") near3 (amorphous or amorphus))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:26
L118	39	L117 and ((ambient or room or ambiant) near2 (temperature))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:26
L120	2	L117 and (reactive near2 evaporat\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:28
L121	15	L117 and (electron ad) beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:28
L122	39	L117 and ((ambient or room or ambiant) near2 (temperature))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:29
L123	2	L117 and (reactive near2 evaporat\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:29
L124	15	L117 and (electron adj beam)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:29
L125	135	L117 not (L122 or L123 or L124)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:29

L126	9	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") same ((react\$5 or O2 or oxygen or "O.sub.2") near3 (vaporiz\$8 or evaporat\$5))) and ((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with amorphous)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:33
L127	384	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (amorphous or porous or pore or porosity or density or amorphus or coat\$5 or deposit\$5 or film or layer or \$4cvd or \$4pvd or vaporiz\$8 or evaporat\$6 or vapors\$5 or deposit\$5 or coat\$5 or process or vaporiz\$8 or \$4cvd or \$4pvd or \$4pvd or sputter\$5)) and ((evaporat\$5 or deposit\$5 or coat\$5 or process or vaporiz\$8 or \$4cvd or \$4pvd or sputter\$5) near6 (interrupt\$7 or plural\$6 or stop\$5 or multi or multiple or two or several or pause or paused or pausing) near6 (cool\$5 or temperature))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:49
L128	16	127 and 47	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:38
L129	368	127 not 128	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:40

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L130	26	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3") with (amorphous or porous or pore or porosity or density or amorphus or coat\$5 or deposit\$5 or film or layer or \$4cvd or \$4pvd or vaporiz\$8 or evaporat\$6 or vapor\$8 or sputter\$5)) same ((evaporat\$5 or deposit\$5 or coat\$5 or process or vaporiz\$8 or \$4cvd or \$4pvd or sputter\$5) near6 (interrupt\$7 or plural\$6 or stop\$5 or multi or multiple or two or several or pause or paused or pausing) near6 (cool\$5 or temperature))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:52
L131	46	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (amorphous or porous or pore or porosity or density or amorphus or coat\$5 or deposit\$5 or film or layer or \$4cvd or \$4pvd or vaporiz\$8 or evaporat\$6 or vapor\$8 or sputter\$5)) and ((interrupt\$7) near6 (cool\$5 or temperature))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 14:57
L132	36	((hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O. sub.3" or "Hf.sub.2 O.sub.3") with (amorphous or porous or pore or porosity or density or amorphus or coat\$5 or deposit\$5 or film or layer or \$4cvd or \$4pvd or vaporiz\$8 or evaporat\$6 or vapor\$8 or sputter\$5) same interrupt\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 15:04
L133	416	((coat\$5 or deposit\$5 or film or layer or \$4cvd or \$4pvd or vaporiz\$8 or evaporat\$6 or vapor\$8 or sputter\$5) near5 interrupt\$5 with cool\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 15:09
L134	9	133 and (hafnia or ((hafnium or Hf) near4 \$30xide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf. sub.2O.sub.3" or "Hf.sub.2 O.sub.3")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 15:06

L135	11	133 and 99	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 15:06
L136	42		US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/14 15:11